

Supporting Information

Reduction of Threading Dislocation Density in Sputtered Ge/Si (100) Epitaxial Films by Continuous-Wave Diode Laser Induced Recrystallization

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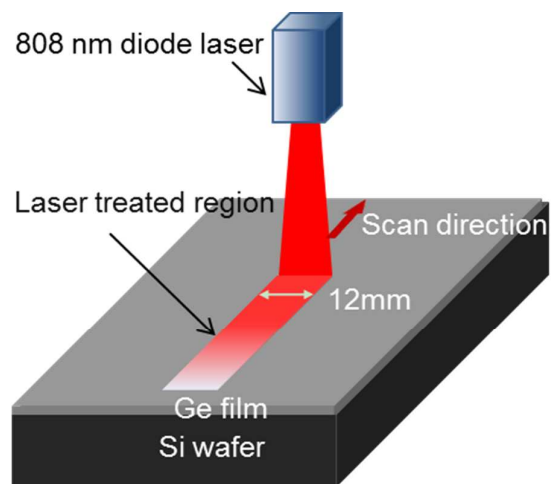


Figure S1. Schematic diagram of the diode laser annealing process